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# I. Introduction

Department of

Plasmonic nanocrescents are of interest as substrates for surfaceenhanced spectroscopies due to their tunable resonance in the visible to mid-IR region and high optical near-fields.<sup>1,2</sup> Due to the asymmetric nature of the nanocrescent structure multiple resonance modes arise, and can be selectively excited by the polarization of the incident light.<sup>3</sup> In order to obtain maximum signal enhancement from a nanostructure in any surface enhanced spectroscopy, the molecule of interest must spatially overlap with the localized near fields of the structure, which simulations have shown to be spatially inhomogeneous.<sup>4</sup> For surface enhanced spectroscopy applications, this leads to an ensemble measurement of non-uniform signal enhancement from the nanostructure. Maximized signal enhancement, and thus better sensitivity, could be achieved by understanding the near field distribution and subsequently localizing molecules of interest in the regions of highest field enhancement. Enhanced second harmonic generation and two photon absorption of photopolymers are used to experimentally probe the near field distribution of nanocrescents.

#### IV. Near Field Enhancement

Finite difference time domain simulations of nanocrescent structures show different near field distributions for short and long axis polarizations.

Charge Distribution

For light polarized along the short axis, electrons oscillate between the backbone and the crescent which enhanced near leads to fields to these localized same regions.

### field distribution of the structures can be mapped through two photon absorption (TPA) of a photopolymer. Near Field E/E







# II. Nanosphere Template Lithography

Nanosphere Template Lithography<sup>3,5</sup> allows for control in the fabrication process which leads to tunability of the localized surface plasmon resonance (LSPR).



Polystyrene beads are used as a mask to fabricate individual structures







Tamer Ali and Peter Nordlander, Rice University, unpublished

0.4

# V. Second Harmonic Generation

We probed enhanced second harmonic generation (SHG) of nanocrescent arrays to understand the near field distribution and nonlinear properties of the nanostructures.





TPA is the simultaneous absorption of two low energy photons to excite a higher energy transition

VI. Near Field Mapping

Since nanocrescents enhance nonlinear processes, the near

- It is an inherently weak process that requires high light intensity, but can be enhanced by near fields of nanostructures
- Exposure with low light intensity leads to spatially selective polymerization in or near regions of near field enhancement





Incident light polarized along short axis of nanocrescents



- Angled metal deposition leads to a shadow on one side of the bead
- Ion beam etching normal to surface removes metal except the metal protected by bead
- Template beads removed with tape



# III. Polarization Dependence

Due to the asymmetry of the structure, multiple plasmon resonance modes arise and can be selectively excited by the polarization of incident light.





light intensity, but can be enhanced by near fields of nanostructures



1800 2000 Wavelength (nm)

- Nanocrescents engineered so that LSPR of both long axis and short axis overlap with 800 nm output of Ti:Sapphire laser
- LSPR spectra show short axis at 65°, long axis at 155°





- Photoresist localized between multiple crescents (tips and backbone)
- Possibly due to coupling of near fields in nanocrescent arrays
- Future work:
  - AFM to understand topology of resist and crescents
  - Probe near field distribution of better defined, isolated nanocrescents

#### VII. References

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#### Polarization of incident light:

• Along the short axis of crescent leads to a higher energy LSPR (shown in red) Along the long axis of crescent leads to lower energy LSPR (shown in blue)

• At angles between short and long axes lead to excitation of both resonances

#### 350

• SHG intensity was monitored as a function of polarization angle of incident light

• Minima in signal occur at 65°, corresponds to short axis

Maxima in signal occur at 155°, corresponds to long axis

Signal enhancement from both polarizations, but order of magnitude difference, indicating different field distributions and intensities

Enhancement of nonlinear process

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